

(19)
(12)

(KR)
(B1)

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H01L 21/28

(45)
(11)
(24)

2002 05 13
10 - 0324020
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(21) 10 - 1998 - 0035019
(22) 1998 08 27

(65) 2000 - 0015238
(43) 2000 03 15

(73)

136 - 1

(72)

105 - 907

(74)

:

(54)

1 , 2 가 , 1 2 , 2
가 .

도 2c

1a 1d

2a 2c

11,21 : 13,23 : 1

15,25 : 17 : 2

19,27 :

가 (Al) 가 (Physical Vapor Deposition, PVD)
 가 (chemical vapor deposition, CVD)

가 (chemical vapor deposition, CVD)

1a 1d

(21) (23) (25)
 (25) TiN (1a, 1b)

(27) (25) (25)
 (27) MOCVD

(27) 2000 (sub micron)
 가

WN , MOCVD 가 TiN
 .(1c, 1d)

ylidichlorosilane) DMDCS (dimeth

1 ,
 1 ,
 2 가 ,
 2

2a 2c .
 , (15) (11) 1 (13) TiN (15)
 , (15) (15) ()
 , (2a) (15) 2 (17)
 , (2b) 2 (17) (15)
 , 가 2 (17)

, MOCVD (15) (19) .
 , (19) (15) , 2 (19) (17)
 (19) , (2c)
 , (11) , (11)

가 . , 가

(57)

1.

1 ,

1 ,

2 가 , 2

2.

1 ,

1 2

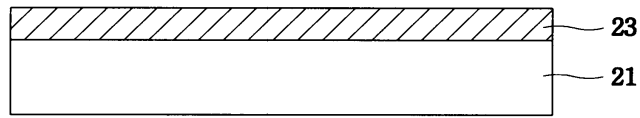
3.

1 , TiN WN

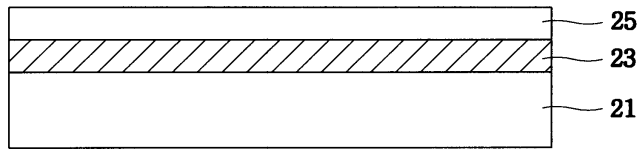
4.

1 , MOCVD

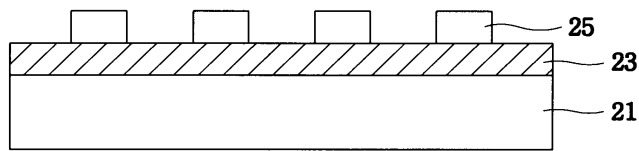
1a



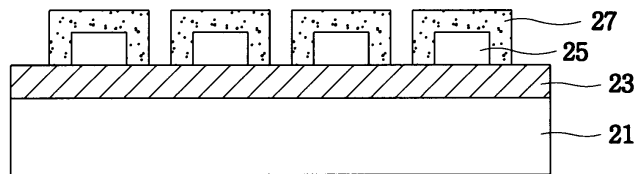
1b



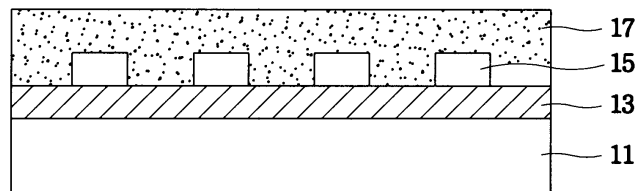
1c



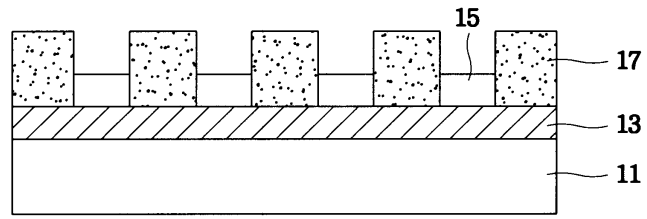
1d



2a



2b



2c

